

## Electronic Patent Application Fee Transmittal

Application Number:	10591718			
Filing Date:	05-Sep-2006			
Title of Invention:	Positive-type resist composition for liquid immersion lithography and method for forming resist pattern			
First Named Inventor/Applicant Name:	Keita Ishiduka			
Filer:	Nichole Elizabeth Martiak/Kathleen Goodhand			
Attorney Docket Number:	1608-7 PCT/US			
Filed as Large Entity				
<b>U.S. National Stage under 35 USC 371 Filing Fees</b>				
Description	Fee Code	Quantity	Amount	Sub-Total in USD(\$)
<b>Basic Filing:</b>				
<b>Pages:</b>				
<b>Claims:</b>				
Claims in excess of 20	1615	2	52	104
<b>Miscellaneous-Filing:</b>				
<b>Petition:</b>				
<b>Patent-Appeals-and-Interference:</b>				
<b>Post-Allowance-and-Post-Issuance:</b>				
<b>Extension-of-Time:</b>				

Description	Fee Code	Quantity	Amount	Sub-Total in USD(\$)
<b>Miscellaneous:</b>				
Request for continued examination	1801	1	810	810
<b>Total in USD (\$)</b>				<b>914</b>